

REMARKS

Reconsideration of the present invention in view of the above amendments and the following remarks is respectfully requested.

Status of the claims:

Claims 1-30 are pending. Claims 15, 17, 20, 22, 23, and 25-30 have been allowed. Claims 1-3, 8-10, 16, 18, 19, 21, 24 have been rejected. Claims 4-7 and 11-14 have been objected to. Claims 1-3, 8-10, 18-19, and 24 have been cancelled herein. Claims 4 and 12 have been amended herein. New Claims 31-35 have been added herein.

Allowance of Claims 15, 17, 20, 22, 23, and 25-30:

The Applicant thanks the Examiner for the allowance of the above claims. The Applicant respectfully points out that the allowed claim 15 need not be limited by the requirement that "the cyclosiloxane be stabilized and be able to be used in a chemical vapor deposition process" as stated by the Examiner. In some embodiments, the cyclosiloxane can be stabilized by the free radical scavenger alone or in combination with one or more polymerization inhibitors disclosed within the application or known within the art. Further, while the application and the allowed claims recite stabilizing cyclosiloxanes for chemical vapor deposition processes, the present invention is not to be construed as being limited thereto. It is anticipated that the present invention may be suitable for other applications where a stabilized cyclosiloxane is needed.